

研究スタッフ

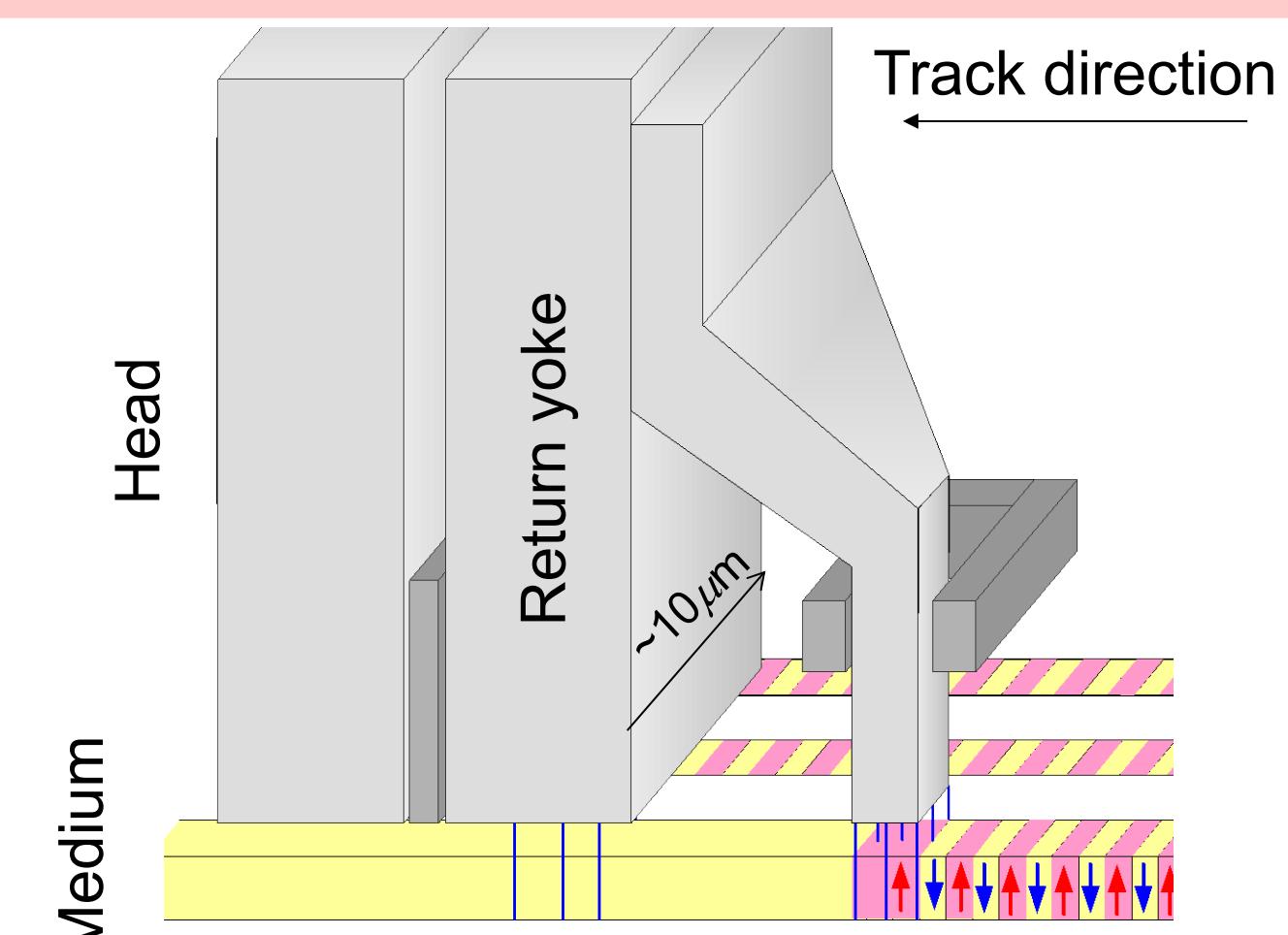
教授：齊藤 伸、准教授：角田 匡清
助教：小川 智之、技術職員：小野寺 政信
研究員：飛世 正博、日向 慎太朗

研究目的

本研究室では、スパッタ法を中心としたドライプロセスならびに化学合成を中心としたウェットプロセスを駆使することによって、超高密度磁気記録媒体、高性能・高感度を有するMRAM・SVヘッドおよび高周波デバイスを実現し得る、新たな材料設計・プロセス技術の確立を目指している。

主な研究テーマ

HDD beyond 1 Tb/inch²



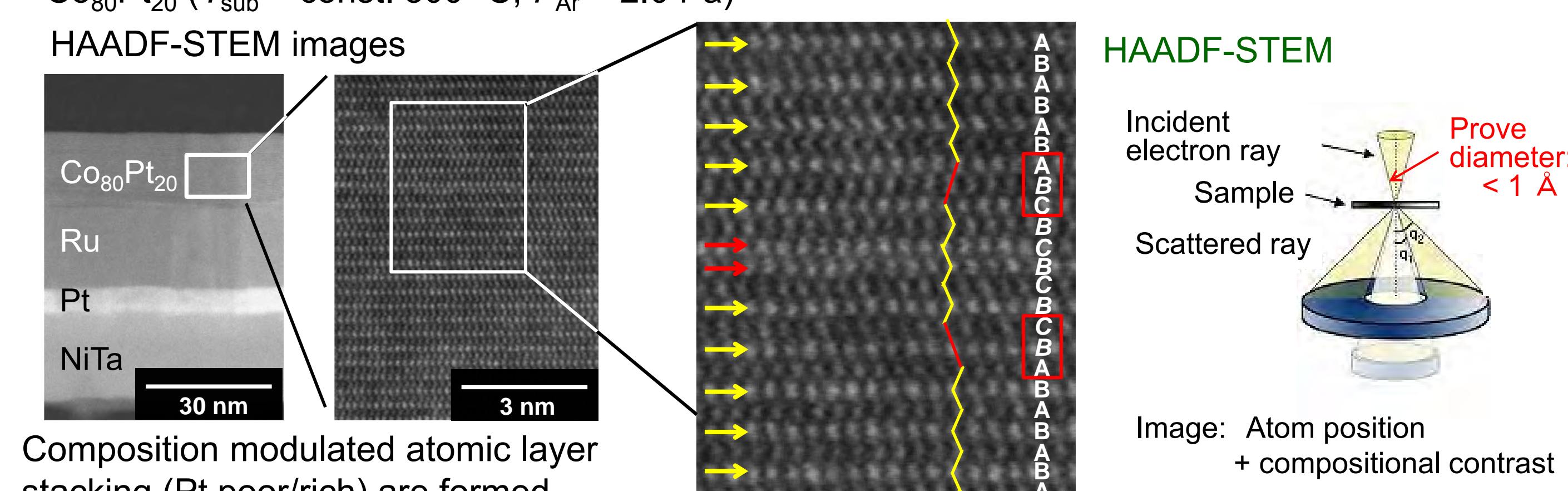
Media structure for perpendicular recording

In-line UHV sputtering machine



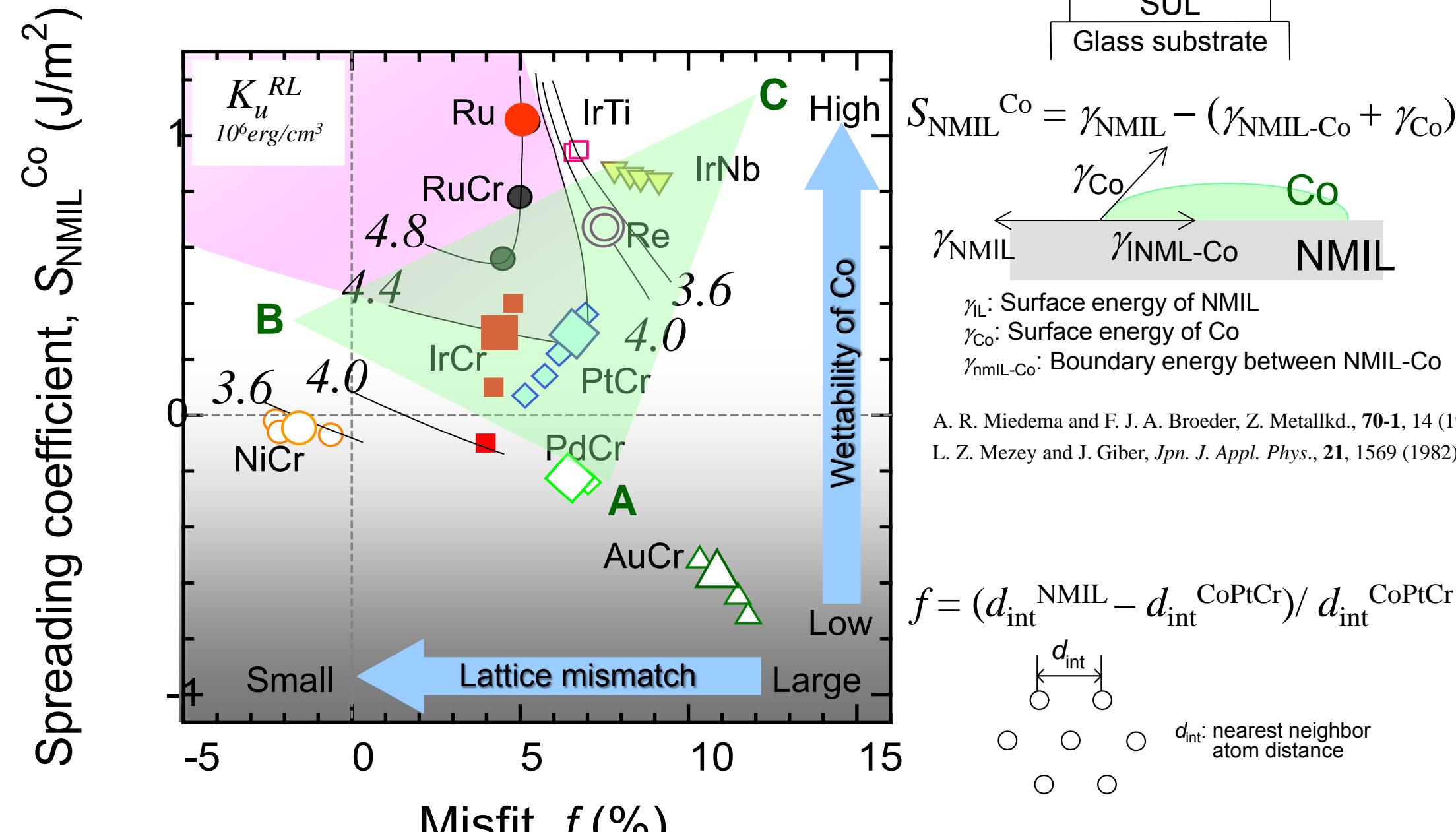
Composition modulated atomic layer stacking for high- K_u material

$Co_{80}Pt_{20}$ (T_{sub} = const. 300 °C, P_{Ar} = 2.0 Pa)

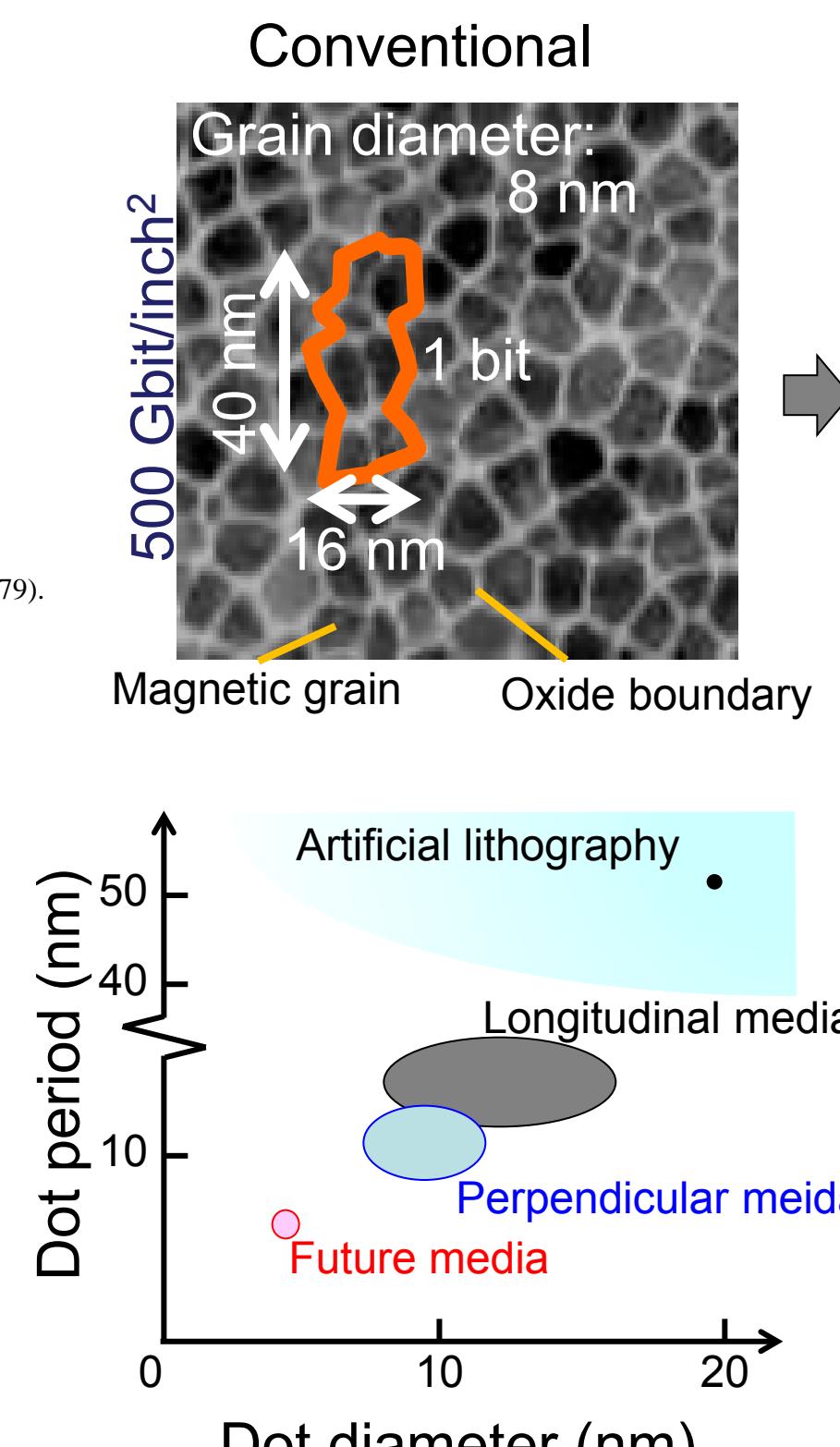


Fcc stacking as faults in macroscopic of hcp phase accompanies with irregularities for the periodicity of the compositional modulation

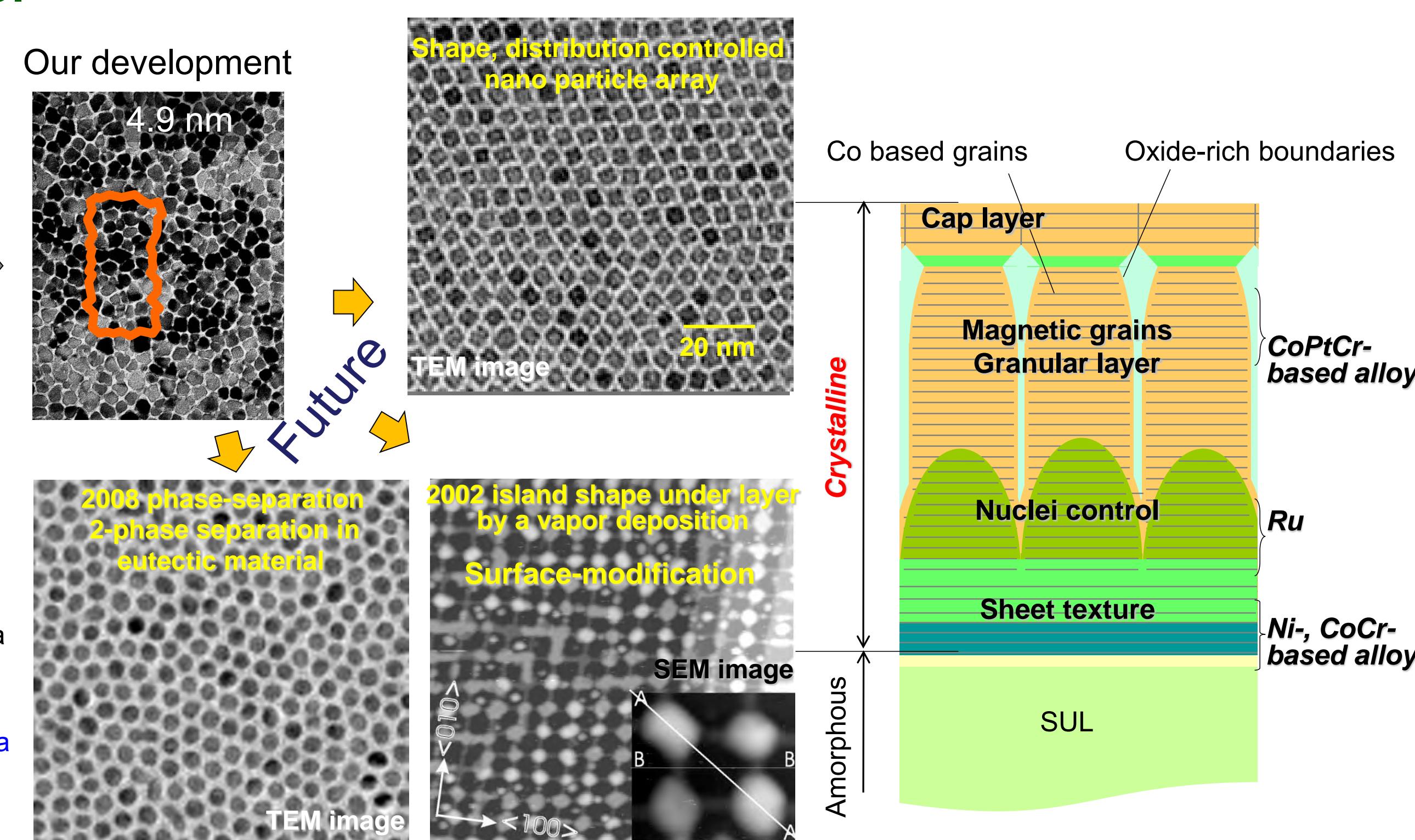
Alternative material to Ru



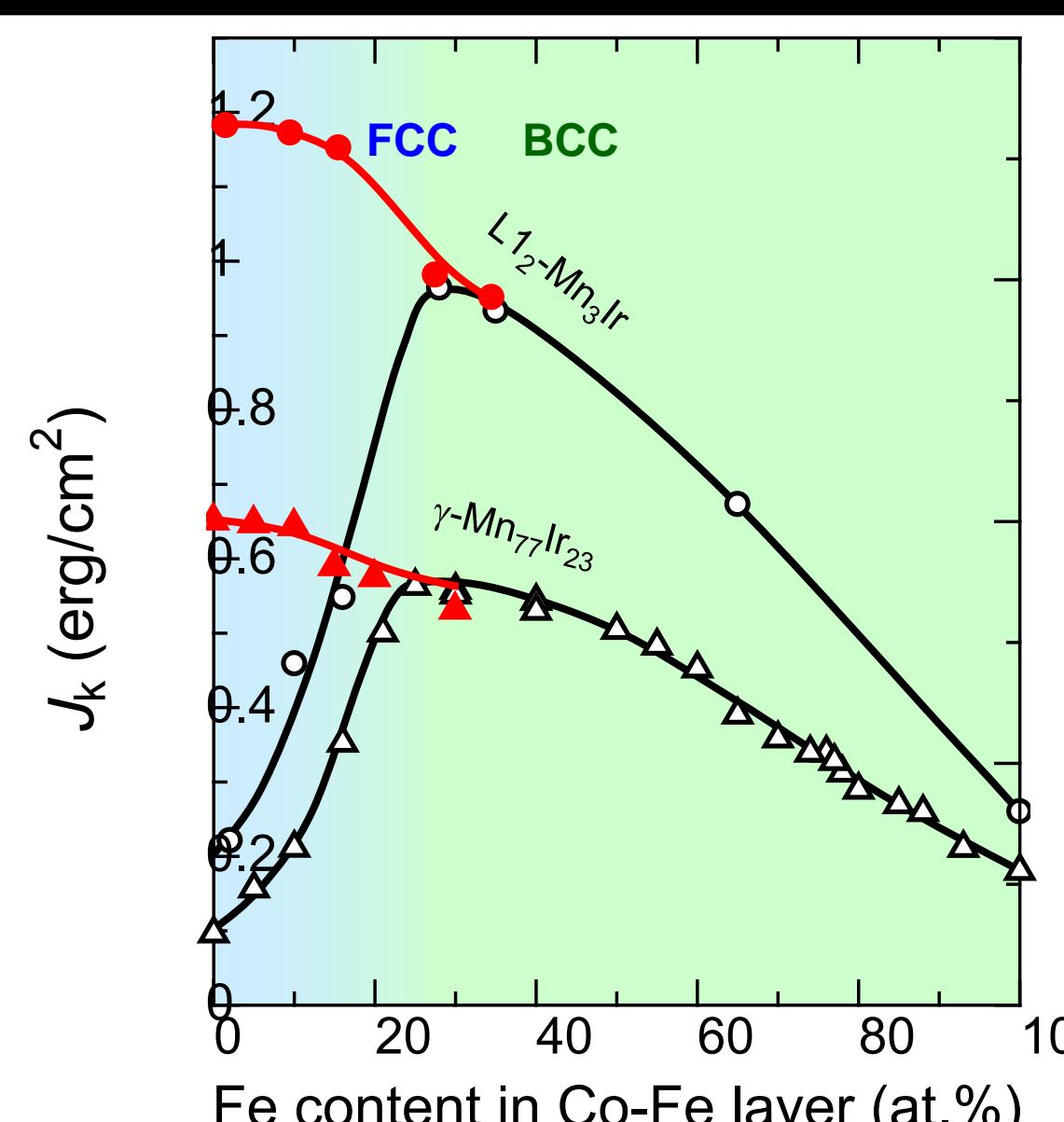
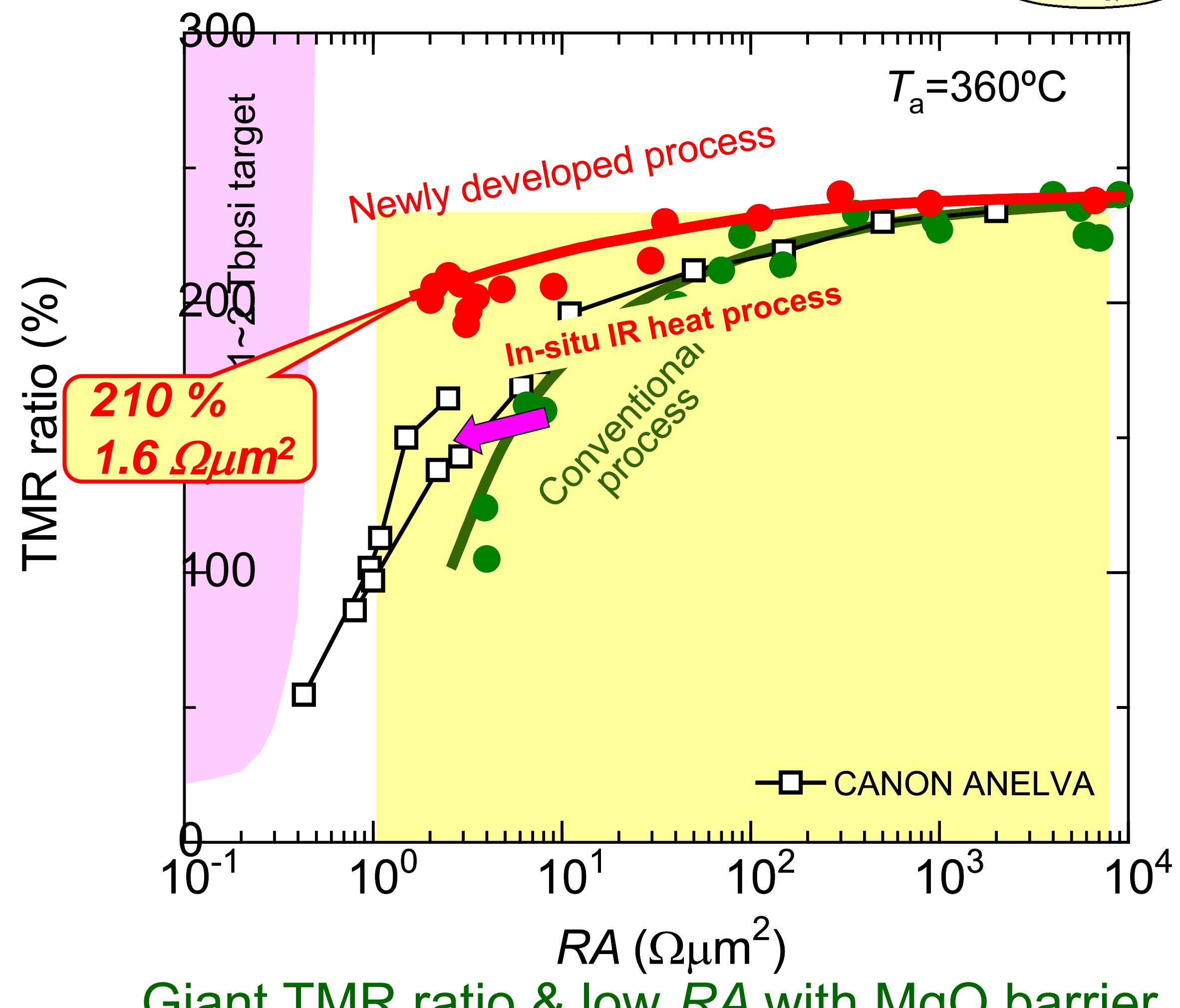
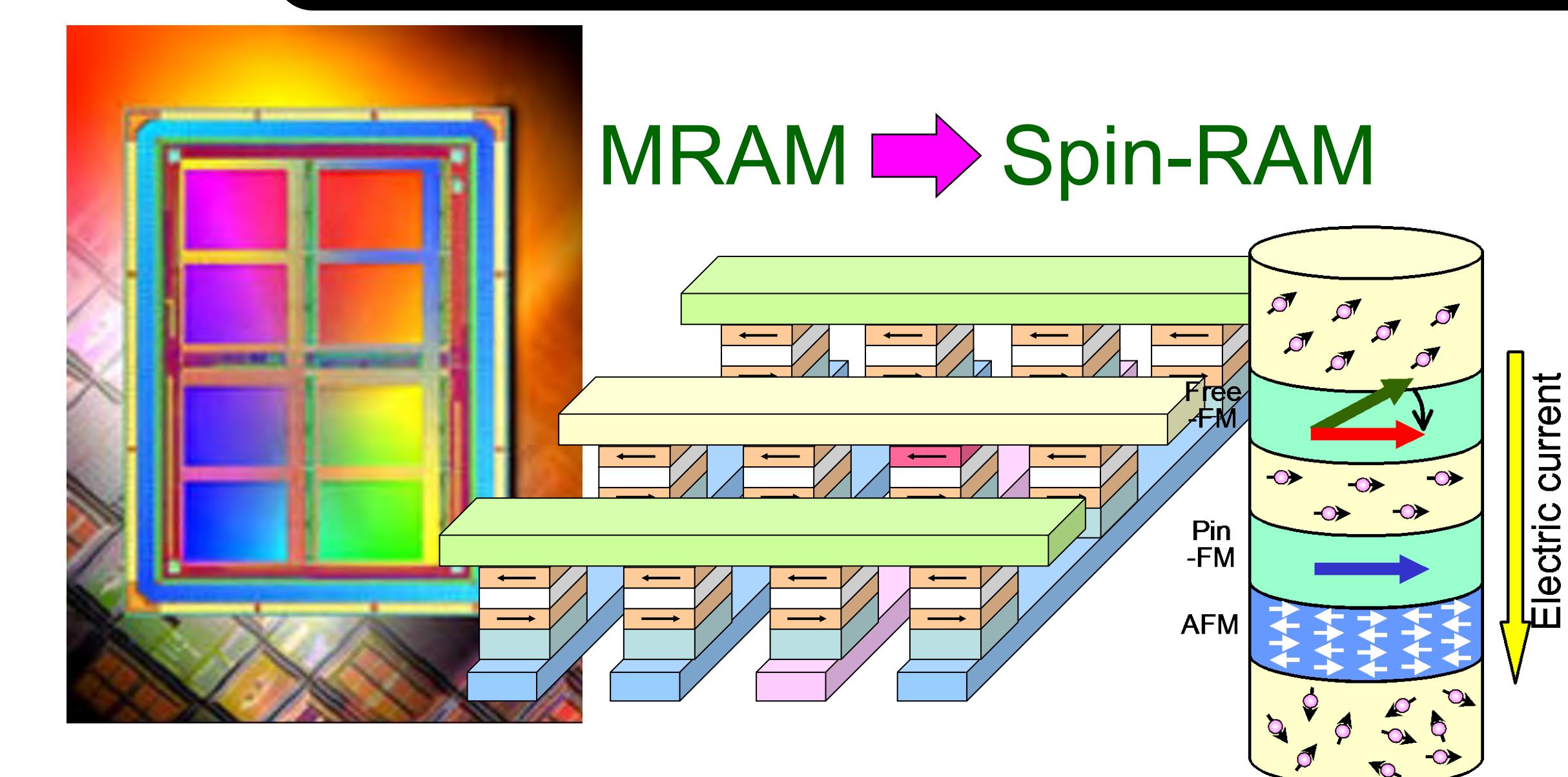
Microstructure control



Ordered-arrangement structure by a self-assemble phenomenon



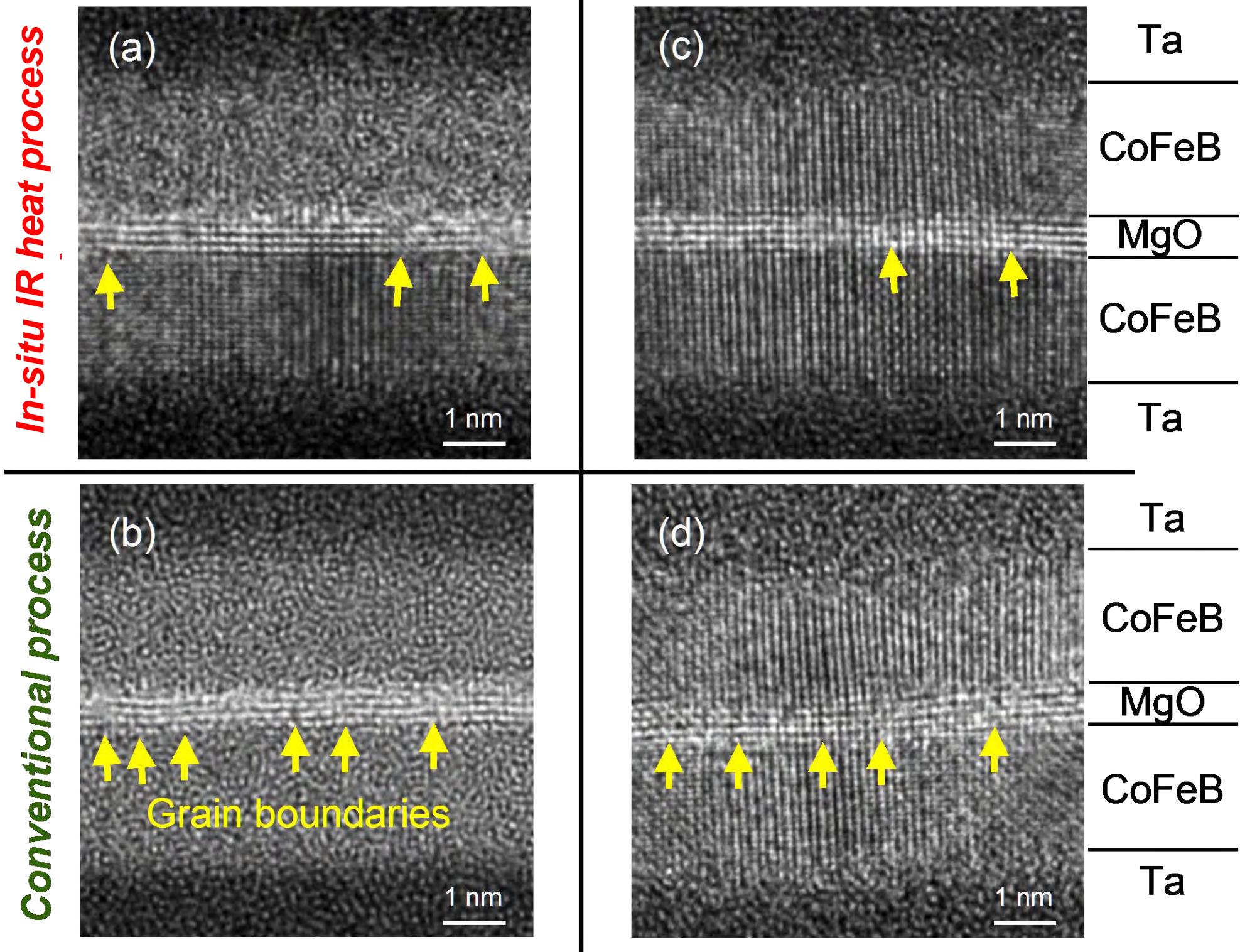
Spin nano technology for high performance magnetoresistive random access memory



Enhanced exchange bias property with ultra-thin insertion layer

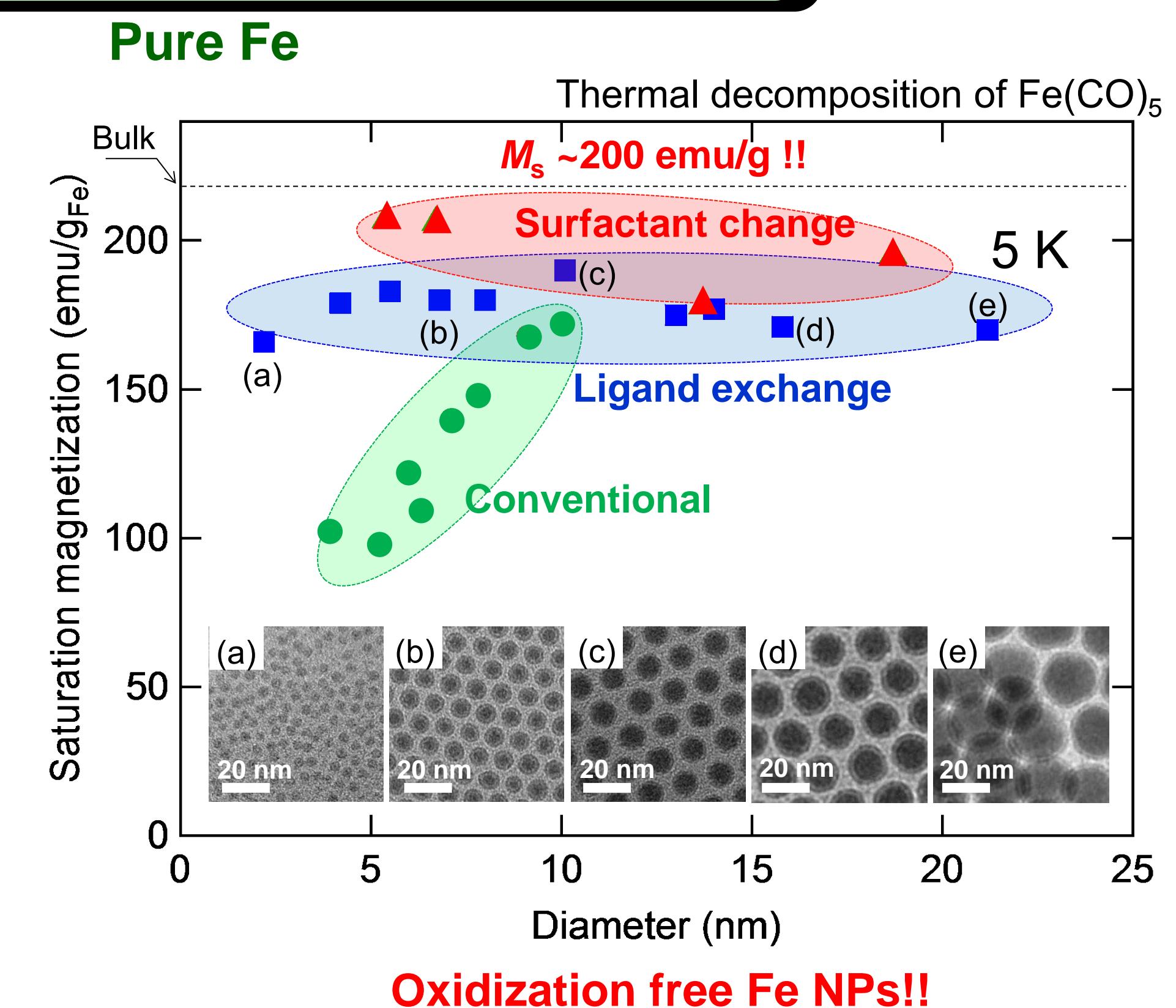
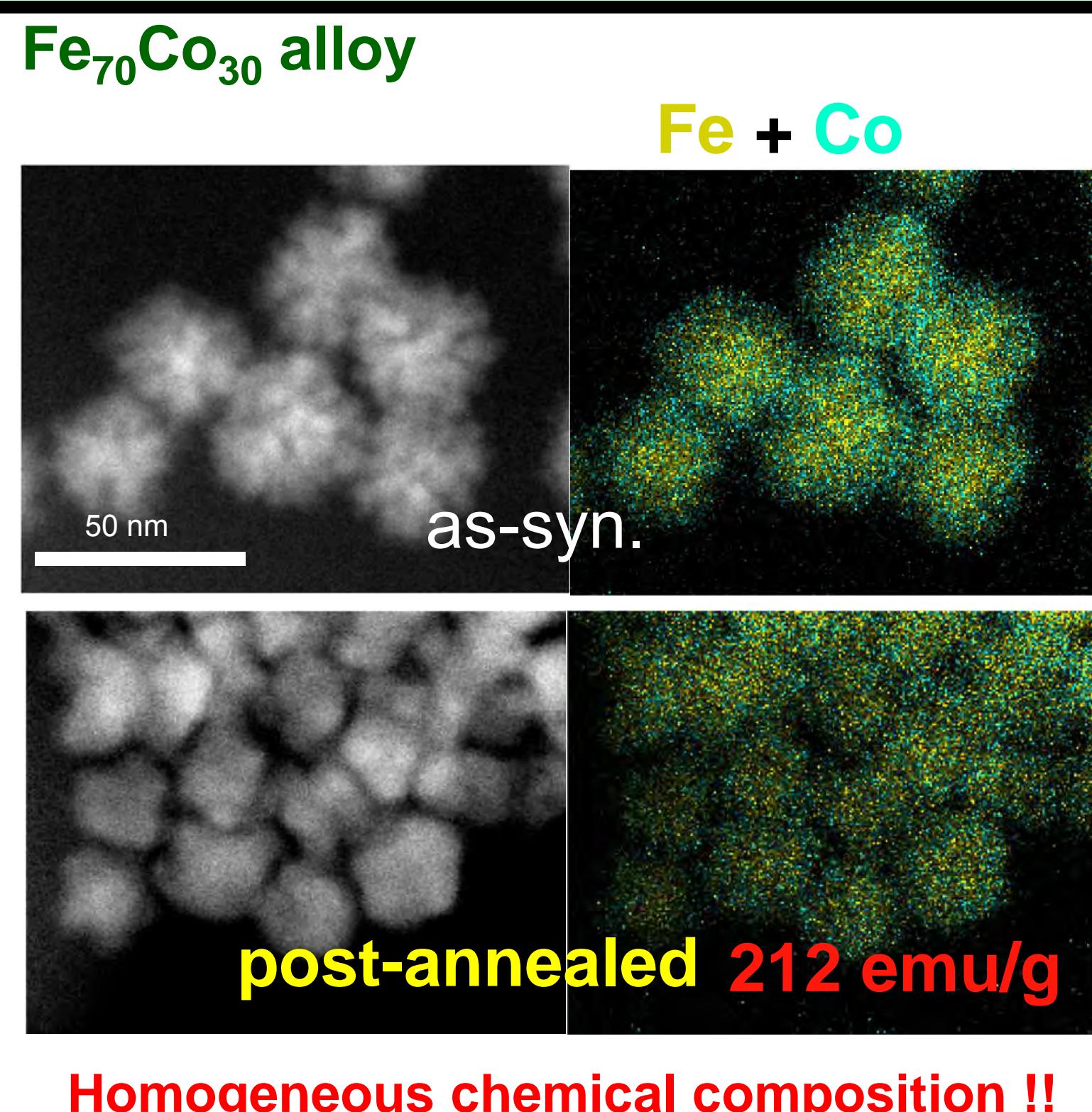
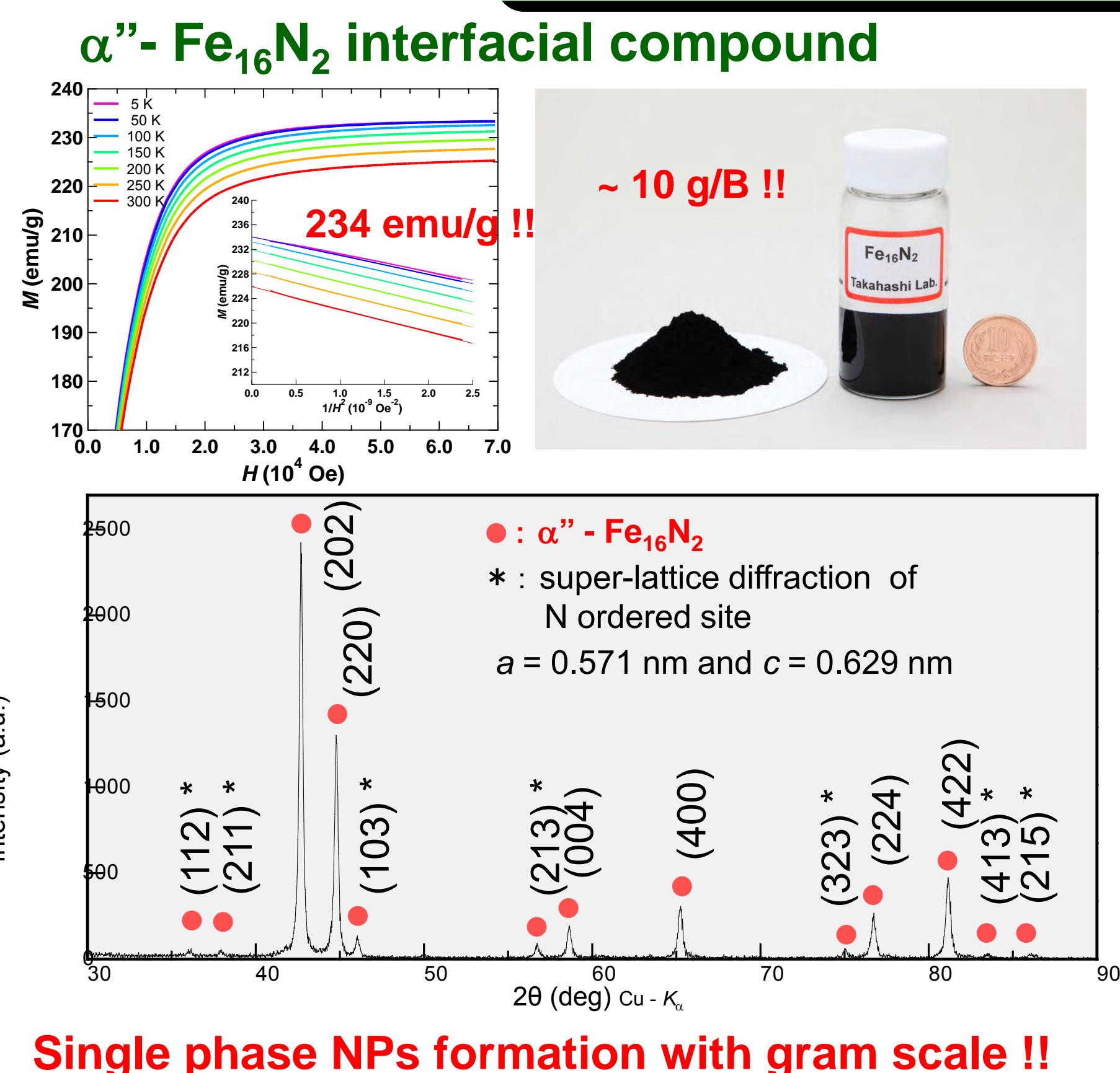
As-deposited.

360°C Post annealed

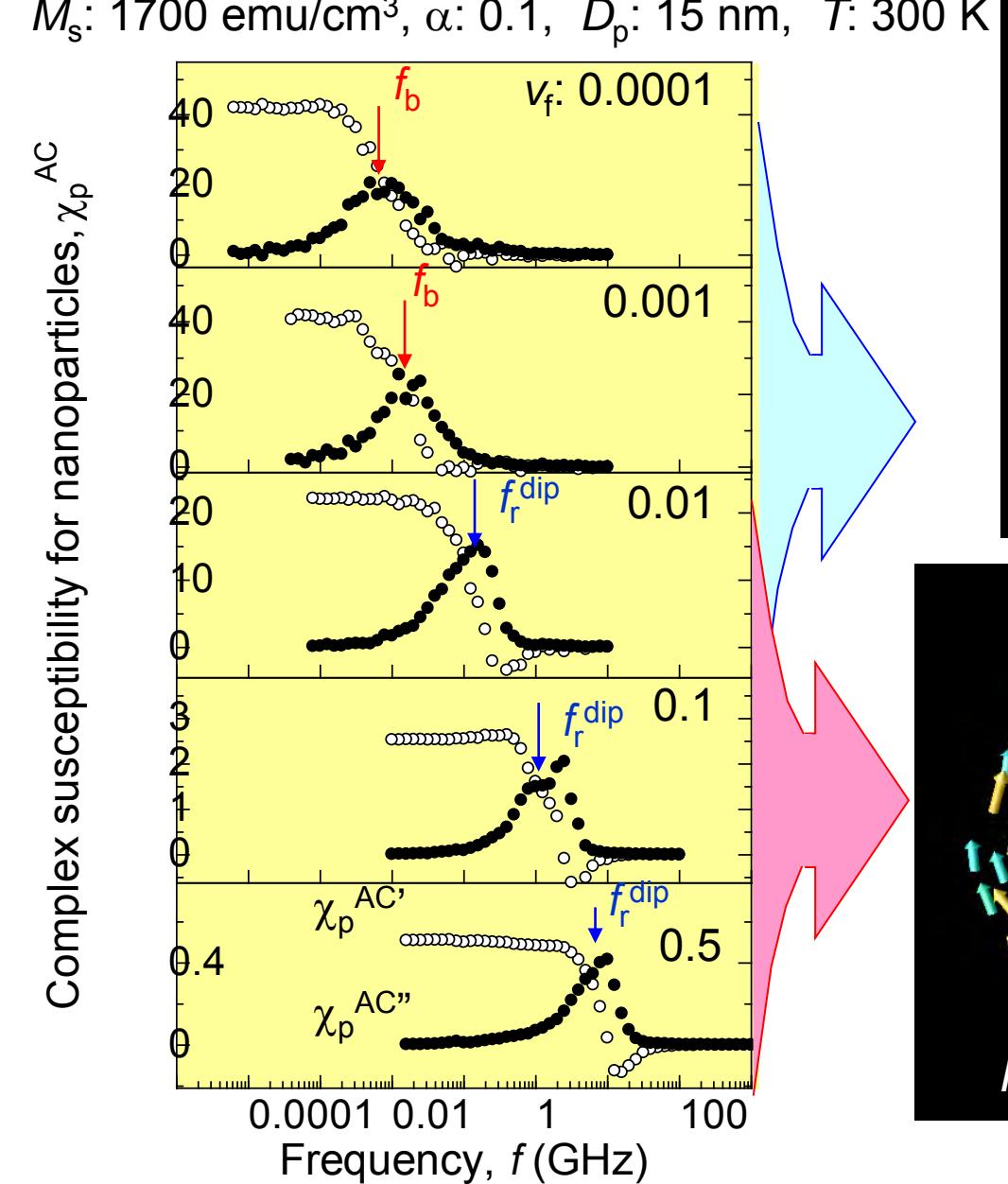
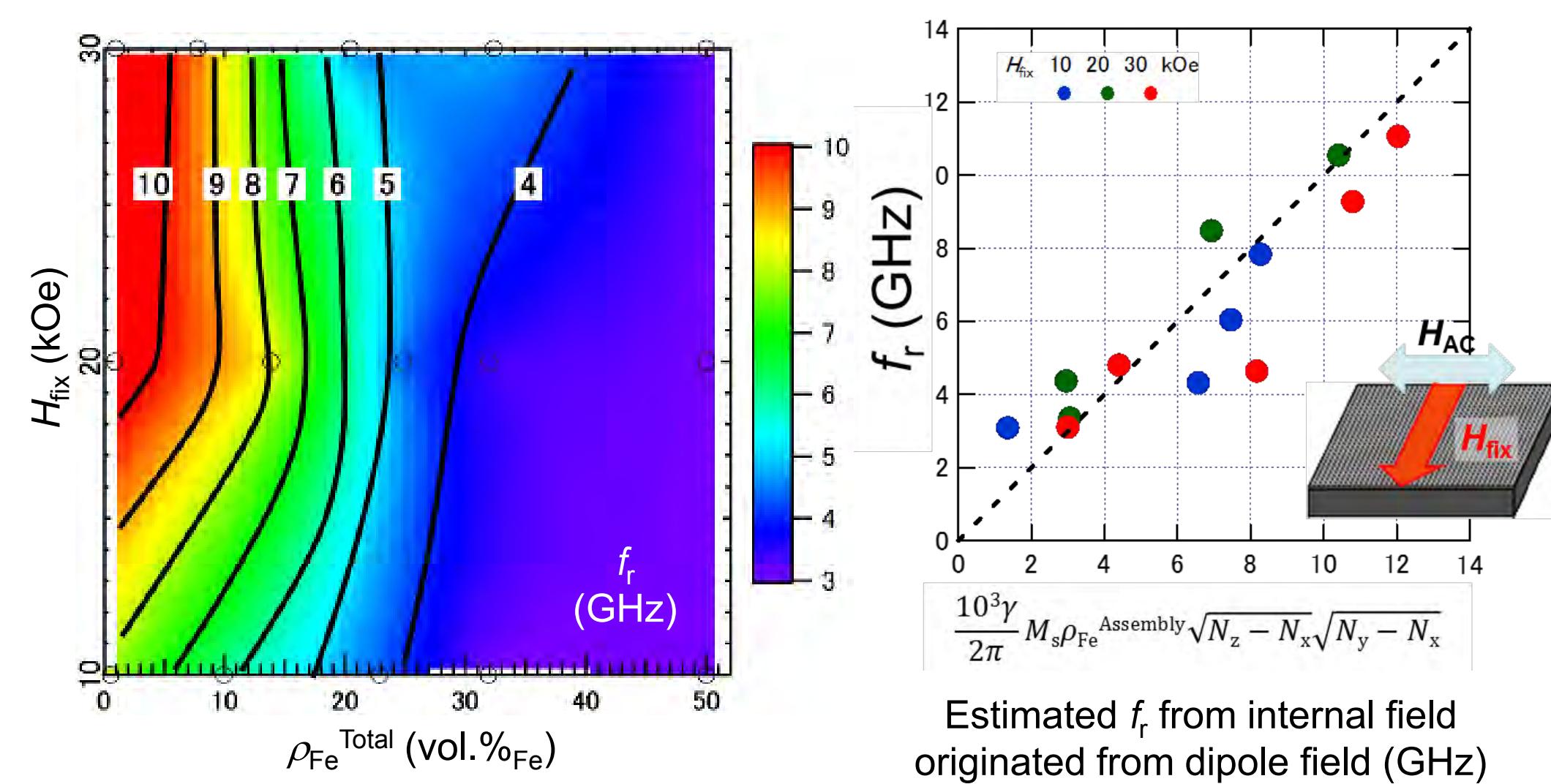


Promoting lateral grain size of the MgO barrier by the in-situ IR heat treatment

Fe-based magnetic nanoparticles for new magnetic devices



Challenge to GHz-band magnetic response



Strong dipole interaction field enhances $f_r > 10 \text{ GHz} !!$

Compression molding

